

EUROPEAN PATENT OFFICE

Patent Abstracts of Japan

PUBLICATION NUMBER : 04342112
PUBLICATION DATE : 27-11-92

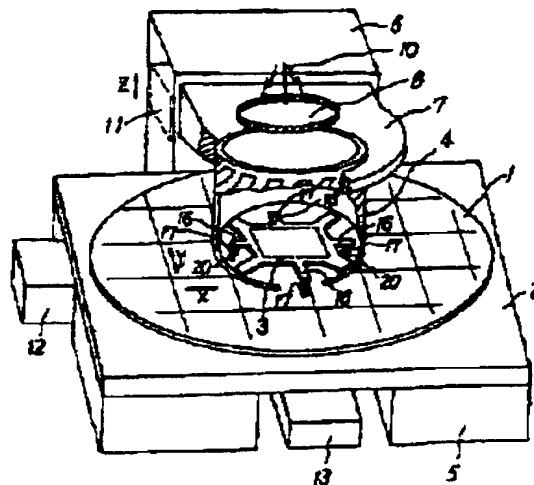
APPLICATION DATE : 17-05-91
APPLICATION NUMBER : 03140697

APPLICANT : OLYMPUS OPTICAL CO LTD;

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INT.CL. : H01L 21/027 G03F 9/00

TITLE : X-RAY LITHOGRAPHIC APPARATUS



ABSTRACT : PURPOSE: To provide an X-ray lithographic apparatus which can form a desired pattern with good accuracy and which can manufacture a ULSI easily.

CONSTITUTION: In an X-ray lithographic apparatus, a wafer 1 is irradiated, via an X-ray mask 3, with X-rays 10 from an X-ray source 25 and the pattern of said X-ray mask 3 is drawn on the wafer 1. In the X-ray lithographic apparatus, the following are provided: STM or AFM probes 17 installed at the X-ray mask 3; and a control means 4 which controls a relative position between the X-ray mask 3 and the wafer 1. The apparatus is constituted so as to control the relative position between said X-ray mask 3 and the wafer 1 via the control means 4 on the basis of the output of the STM or AFM probes 17.

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